

TITLE PAGE

Class	:	BE - 8
Roll. No	:	42428
Assignment No.	:	B. 1b , 1c
Assignment Name	:	2 input CMOS NAND & AND Gates
Date Of Performance	:	12-11-2020

Theory:

F = 90 nm

Symbols

2 ilp nand gate



$$Y_{\text{nand}} = \overline{A \cdot B}$$

2 ilp AND gate.



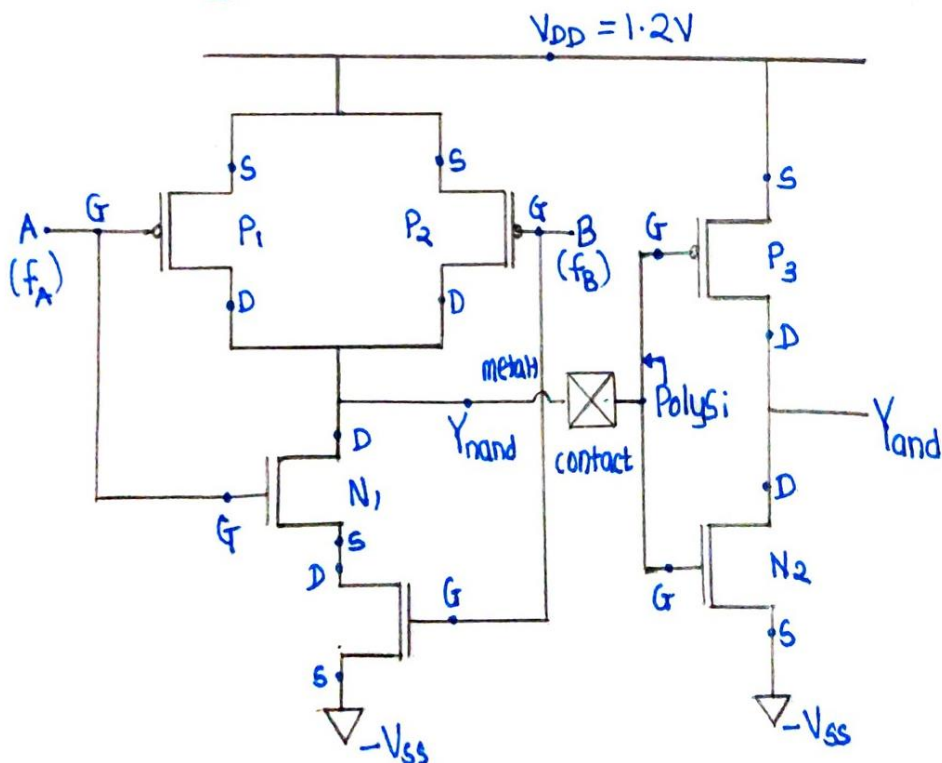
$$Y_{\text{and}} = A \cdot B$$

A	B	Y_{nand}
0	0	1
0	1	1
1	0	1
1	1	0

A	B	Y_{and}
0	0	0
0	1	0
1	0	0
1	1	1

Truth Tables

Combined Schematic:



$$f_B = 2f_A$$

Size of each PMOS Transistor (P_1, P_2, P_3)

$$P = \left(\frac{500}{100} \right) \text{nm} = 5$$

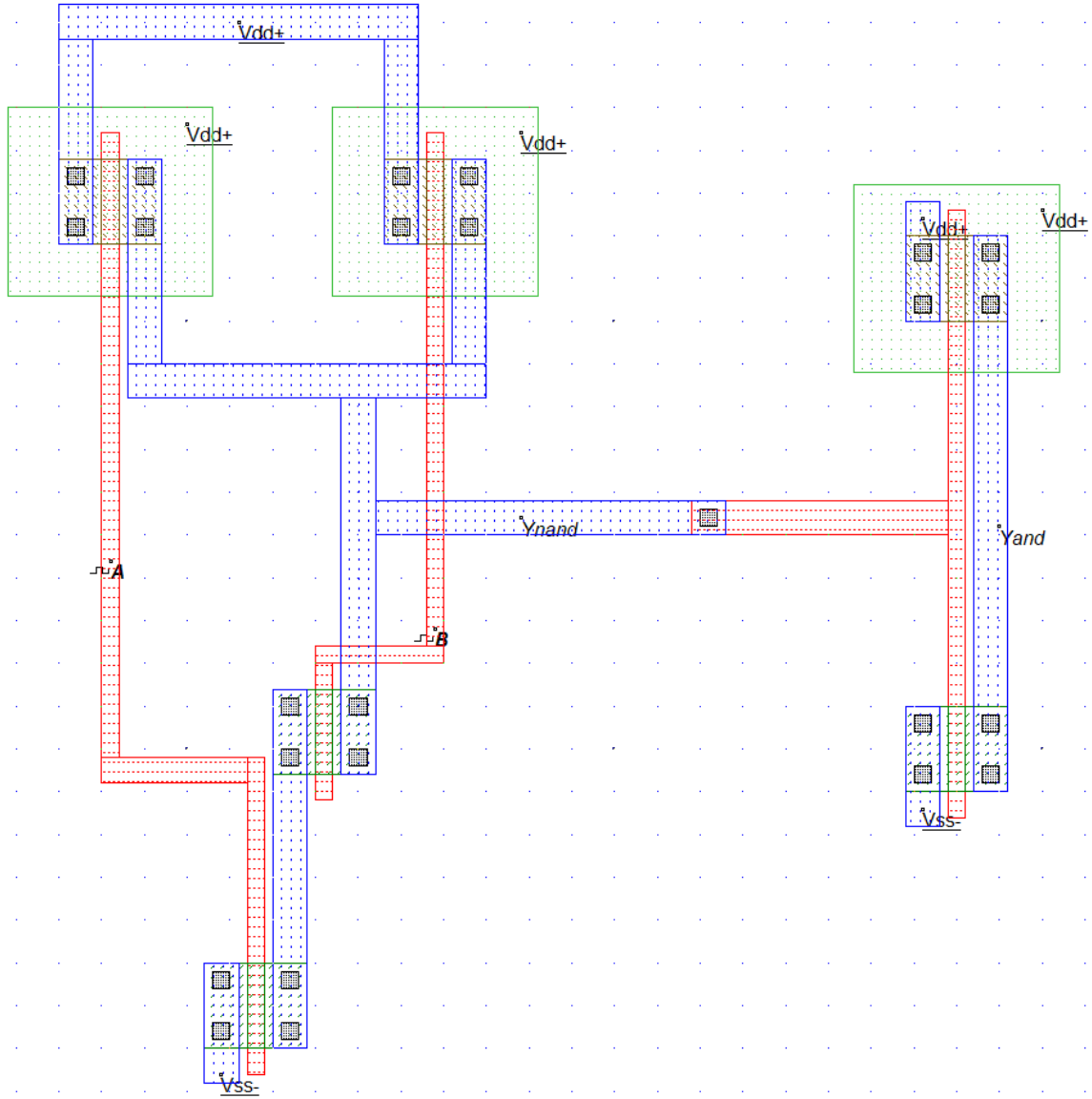
Size of each NMOS Transistor (N_1, N_2, N_3)

$$n = \left(\frac{500}{100} \right) \text{nm} = 5$$

$$\text{Relative Size} = \frac{P}{n} = 1$$

LAYOUT

5 lambda
0.250um



Palette

Options

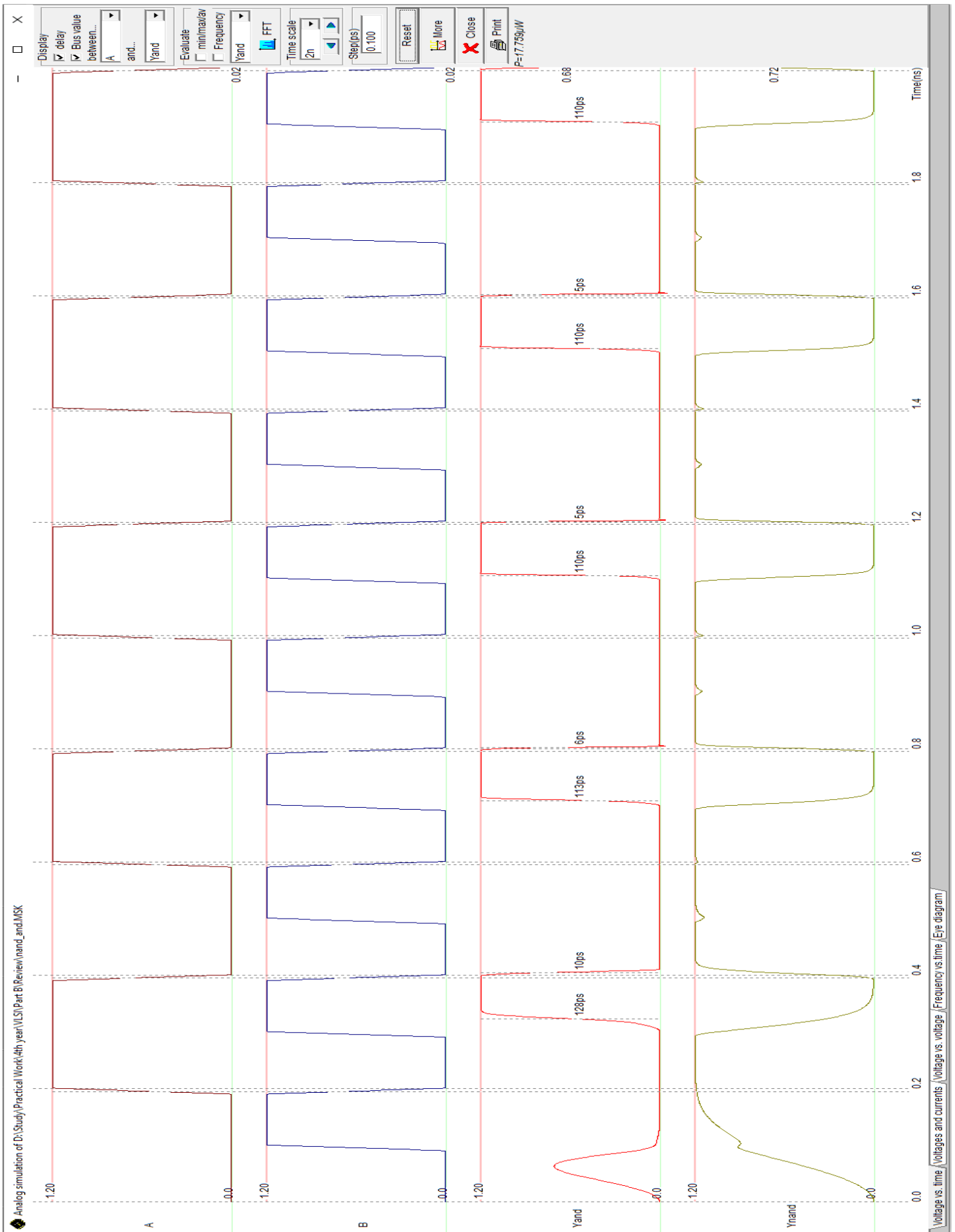
- Metal 6
- Metal 5
- Metal 4
- Metal 3
- Metal 2
- Metal 1
- Polysilicon 2
- Contact
- Polysilicon
- P+ Diffusion
- N+ Diffusion
- N Well

Show palette menu...

Vdd

CMOS 90nm, 6 Metal Copper - strained SiGe - LowK (1.20V,2.50V)

Waveforms



Conclusion:

Thus we have :

- 1) Drawn the LAYOUT for CMOS NAND & AND Gates using 90 nm Foundry.
- 2) Simulated the LAYOUT to observe waveforms & verified its functionality as per TRUTH-TABLE.